

Image

202450US0



IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

ATSUSHI SHIOTA ET AL.

: GROUP ART UNIT: 1712

SERIAL NO: 09/770,289

: EXAMINER: FEELY, M.

FILED: JANUARY 29, 2001

: RCE FILED: HEREWITH

FOR: PROCESS FOR PRODUCING
SILICA-BASED FILM, SILICA-
BASED FILM, INSULATING FILM,
AND SEMICONDUCTOR DEVICE

AMENDMENT

COMMISSIONER FOR PATENTS
ALEXANDRIA, VA 22313-1450

SIR:

Further to the Request for Continued Examination filed herewith, and in response to the Final Rejection dated June 9, 2003, please amend the application identified above as follows.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.